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PATENT

#2/a
5-9-02

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re application of: Hirohiko MURAKAMI et al.

Serial No.: Not Yet Assigned
(PCT/JP01/02885)

Filed: November 30, 2001

For: METHOD FOR PREPARING POROUS SOG FILMS

PRELIMINARY AMENDMENT

Commissioner for Patents
Washington, D.C. 20231

November 30, 2001

Sir:

Prior to the calculation of the filing fees of the above application, please amend the application as follows:

IN THE CLAIMS:

Please amend claims 12, 14 and 15 as follows:

A¹

12. (Amended) The method for preparing a porous SOG film as set forth in claim 8 wherein said heat-treatment is carried out in two stages: in a first stage, said porous film is treated at temperatures ranging from 200 to 350°C to thus mainly evaporate said water and alcohol and in a second stage, said porous film is treated at temperatures ranging from 350 to 450°C to thus finish formation of said porous film, while adhering hydrophilic moieties of surfactant to at least an inner surface of holes present in a resulting porous film and to thus cover inner walls of said holes with hydrophobic moieties of said surfactant, to thus form a porous SiO₂ film.